Voltage-induced magnetic anisotropy change of Fe-4*f*-metal alloys 阪大院基礎工 ^〇田中和仁、三輪真嗣、水落憲和、鈴木義茂 Osaka Univ. [°]K. Tanaka, S. Miwa, N. Mizuochi, and Y. Suzuki

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Voltage-induced magnetic anisotropy change has been investigated because of its potential for non-volatile magnetic random access memories with low power operation. [1,2] Since spin-orbit coupling plays an important role in the voltage-induced anisotropy change, in our previous study, we tested 4*f*-metals since 4*f* metals have large orbital moment. In FeGd alloys, large anisotropy field change and magnetization-energy change ratio have been observed [3]. This suggests that 4*f*-metals are promising for voltage-induced spintronics devices. In this study, we investigated voltage-induced anisotropy change of FeTb(Nd)|MgO|-based magnetic tunnel junctions (MTJs).

V (30 nm) $|Fe_{100-x}(Gd_x, Tb_x Nd_x)|[x = 0-30]|MgO (1.6 nm)|Fe (10 nm) multilayer was fabricated$ by molecular beam epitaxy method on MgO [001] substrate as shown in Fig. 1. The Fe-4*f*metal alloylayer was prepared using co-evaporation of pure Fe and 4*f*metals. The film was patterned into MTJsby using electron-beam lithography and an Ar ion-milling. Fig. 2 shows the normalized magnetizationcurve of Fe (0.55 nm), Fe₉₀Gd₁₀ (0.60 nm) and Fe₉₀Tb₁₀ (0.64 nm) at 0.3 V (-0.3 V), which is calculatedby magnetization curve. From this, the anisotropy field changes of Fe₉₀Gd₁₀ and Fe₉₀Tb₁₀ are largerthan that of Fe.

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Fig.1 Normalized magnetization curves of

(a) Fe (0.55 nm), (b) FeGd (0.60 nm) and (c) FeTb (0.64 nm).

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- [2] T. Maruyama et al., Nature Nanotechnol. 4, 158 (2009).
- [3] K. Tanaka et al., Appl. Phys. Express in press.